Buchalter Docket No.: H9930-0105

## IN THE CLAIMS

Claims 1-17: Canceled.

- 18. (Currently Amended) A planarization composition, comprising:
  - a o-cresol-based polymer compound and a resol phenolic resin;
  - at least one surfactant; and
  - a solvent system comprising at least one alcohol and at least one ether acetatebased solvent.
- 19. (Original) The planarization composition of claim 18, wherein the cresol-based polymer compound comprises a novolac polymer.
- 20. (Original) The planarization composition of claim 18, wherein the at least one alcohol comprises a branched alcohol.
- 21. (Original) The planarization composition of claim 20, wherein the branched alcohol comprises 2-propanol.
- 22. (Original) The planarization composition of claim 18, wherein the at least one ether acetate-based solvent comprises PGMEA.
- Canceled.

- 24. (Previously Presented) The planarization composition of claim 18, wherein the surfactant comprises at least one hydrocarbon surfactant, at least one fluorocarbon surfactant or a combination thereof.
- 25. (Previously Presented) The planarization composition of claim 24, wherein the at least one fluorocarbon surfactant comprises at least one fluoroaliphatic polymeric ester surfactant.
- 26. (Currently Amended) A film comprising the planarization composition of one of claims 1 or claim 18, wherein at least some of the solvent system is removed.

Buchalter Docket No.: H9930-0105

27. (Currently Amended) A film comprising the planarization composition of one of claims 15 or claim 23, wherein at least some of the solvent system is removed.

Claims 28-29: Canceled.

30. (Original) A layered component, comprising:

a substrate having a surface topography; and

a planarization composition of claim 18, wherein the composition is coupled to the substrate.

- 31. (Original) The layered component of claim 30, further comprising at least one additional layer of material or film.
- 32. (Original) A layered component, comprising:

a substrate having a surface topography; and

a layer comprising the film of claim 26, wherein the layer is coupled to the substrate.

- (Original) The layered component of claim 32, further comprising at least one additional layer of material or film.
- 34. (Original) A layered component, comprising:

a substrate having a surface topography; and

a layer comprising the film of claim 27, wherein the layer is coupled to the substrate.

- 35. (Original) The layered component of claim 34, further comprising at least one additional layer of material or film.
- 36. (Currently Amended) A method of forming a planarization composition, comprising:

providing a structural constituent, wherein the structural constituent comprises an ocresol-based polymer compound and a resol phenolic resin;

Buchalter Docket No.: H9930-0105

providing at least one surfactant;

providing a solvent system, wherein the solvent system <u>comprises at least one</u>

<u>alcohol and at least one ether acetate-based solvent</u> is compatible with the

<u>structural constituent and lowers at least one of the intermolecular forces or</u>

<u>surface forces components of the planarization composition</u>; and

blending the structural constituent, the at least one surfactant and the solvent system to form a planarization composition.

Claims 37-38: Canceled.

- (Original) The method of claim 36, wherein the solvent system comprises at least two solvents.
- 40. (Original) The method of claim 39, wherein the solvent system comprises an alcohol-based solvent.
- 41. (Currently Amended) The method of claim [[39]] 40, wherein the alcohol-based solvent comprises 1-propanol or 2-propanol.
- 42. (Currently Amended) The method of claim 39, wherein the solvent system omprises propylene glycol methylether acetate (PGMEA), ethyl lactate, propylene glycol methyl ether, diethylene glycol, <u>2-propanol</u>, acetone or a combination thereof.
- 43. (Original) The method of claim 36, wherein the intermolecular forces component comprises hydrogen bonding interactions, electrostatic forces, steric forces, dipoledipole interactions, dispersion forces, Van der Waals forces or combinations thereof.
- 44. (Original) The method of claim 36, wherein the surface forces component comprises an interfacial surface tension.
- 45. (Previously Presented) The method of claim 44, wherein the solvent system lowers the interfacial surface tension by at least 10%.
- 46. (Previously Presented) The method of claim 45, wherein the solvent system lowers the interfacial surface tension by at least 20%.

Buchalter Docket No.: H9930-0105

47. (Original) The method of claim 36, wherein the planarization composition comprises an apparent viscosity.

- 48. (Previously Presented) The method of claim 47, wherein the solvent system lowers the apparent viscosity by at least 10%.
- 49. (Original) The method of claim 48, wherein the solvent system lowers the apparent viscosity by at least 30%.
- 50. Canceled.

- 51. (Previously Presented) The method of claim 36, wherein the surfactant comprises at least one hydrocarbon surfactant, at least one fluorocarbon surfactant or a combination thereof.
- 52. (Previously Presented) The method of claim 51, wherein the at least one fluorocarbon surfactant comprises at least one fluoroaliphatic polymeric ester surfactant.
- 53. (Currently Amended) A method of forming a film, comprising: providing the planarization composition of claim 18; and evaporating at least part of the solvent system to form a film.
- 54. (Original) The method of claim 53, wherein evaporating at least part of the solvent system comprises applying a continuous source to the planarization composition.
- 55. (Original) The method of claim 54, wherein the continuous source comprises a heat source.
- 56. (Original) The method of claim 55, wherein the continuous source comprises an infrared source, an ultraviolet source, an electron-beam source and combinations thereof.

Claims 57-75: Canceled.